

METHOD OF PROCESSING SUBSTRATE, METHOD OF MANUFACTURING
SEMICONDUCTOR DEVICE, PROGRAM, AND SUBSTRATE PROCESSING

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ABSTRACT

The present disclosure improves the characteristics of a film formed on a substrate. The present disclosure includes: (a) a step in which a raw material is supplied to a substrate; (b) a step in which a reactant is supplied to the substrate; (c) a step in which a regulating agent is supplied to the substrate to regulate the amount of at least one of the molecules of the raw material and the molecules of the reactant adsorbed to the substrate; (d) a step in which at least one of (a) and (b) is performed in an overlapping manner with (c); and (e) a step in which following (d), (a) or (b) that was performed in an overlapping manner with (c) in (d) is performed independently from (c).

Fig. 1